

# **APPARATUS AND METHOD FOR CLEANING SEMICONDUCTOR SUBSTRATES**

## **ABSTRACT OF THE DISCLOSURE**

5           An apparatus for cleaning semiconductor substrates includes a  
chamber having a cleaning room and a drying room disposed over the  
cleaning room. The cleaning room and the drying room are separated or  
placed in communication with one another by a separation plate. An  
exhaust path is formed at a central portion of the separation plate. As de-  
10 ionized water (DI water) filling the cleaning room is drained during a dry  
process, the inside of the drying room is decompressed, and a drying  
fluid in the drying room flows from the drying room to the cleaning  
room along the exhaust path.